

# X-ray Free Electron Laser Part-1 Accelerator

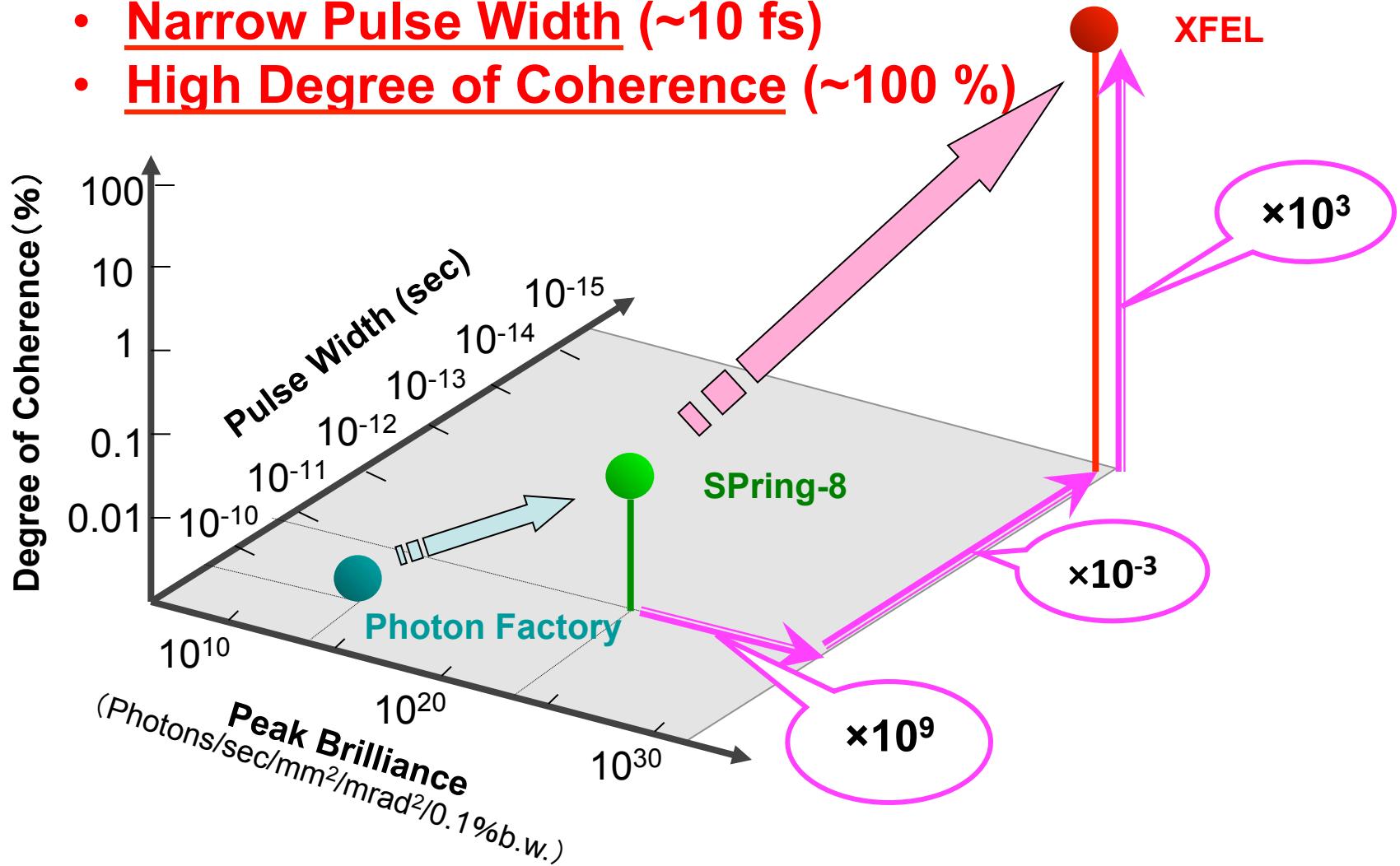
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RIKEN SPring-8 Center  
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# Outline

1. Introduction –What we can observe using XFEL
2. Overview of SASE XFEL
3. Approach to compact XFEL
4. Performance of XFEL

# Remarkable Features of XFEL

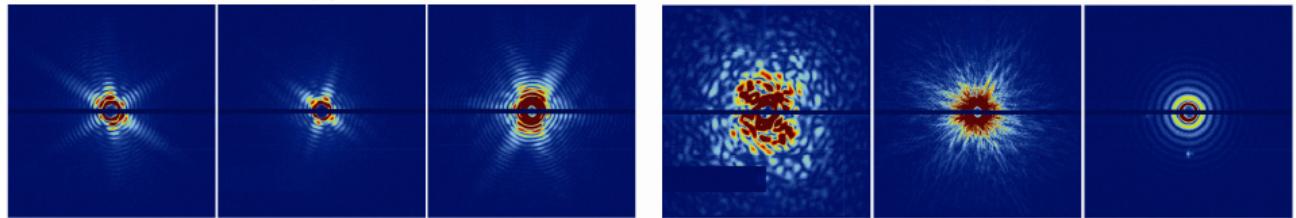
- High Peak Brilliance ( $\sim 10^{33}$ )
- Narrow Pulse Width ( $\sim 10$  fs)
- High Degree of Coherence ( $\sim 100\%$ )



# 1. What XFEL enables us to observe

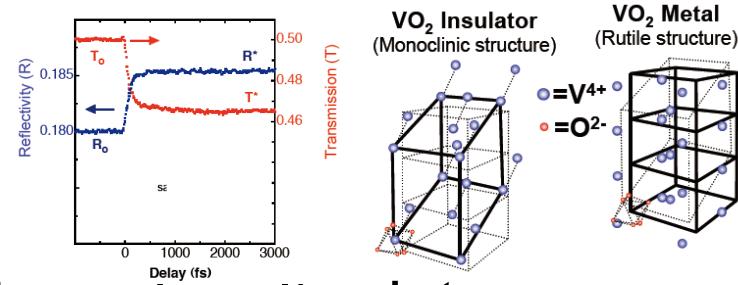
## Coherence

Structure analysis on non-crystalline material (e.g., amorphous, single particle)



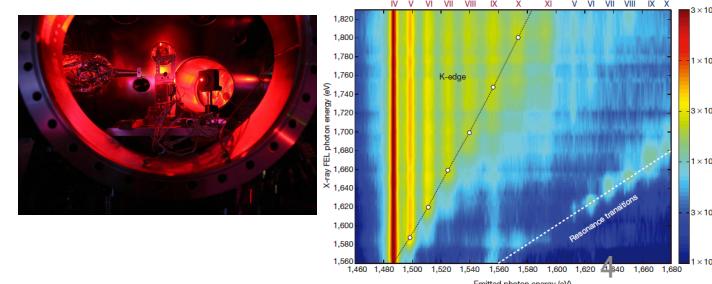
## Ultrafast

Structure/Electric properties probed with fs temporal resolution  
(e.g. ultrafast phase transition)



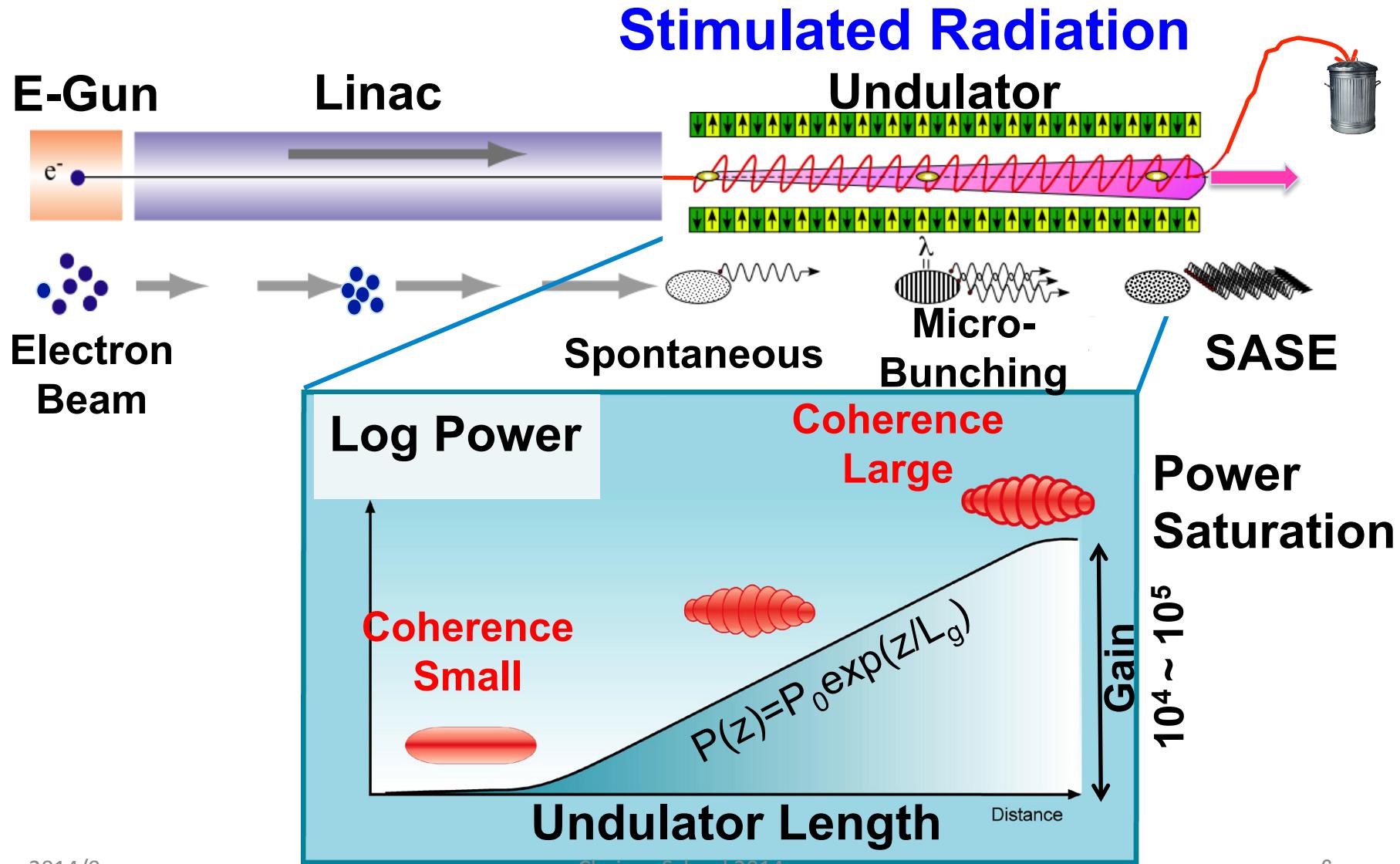
## Peak Brilliance

Physics in highly-excited/extreme state under ultra-intense optical field (e.g. high density state)



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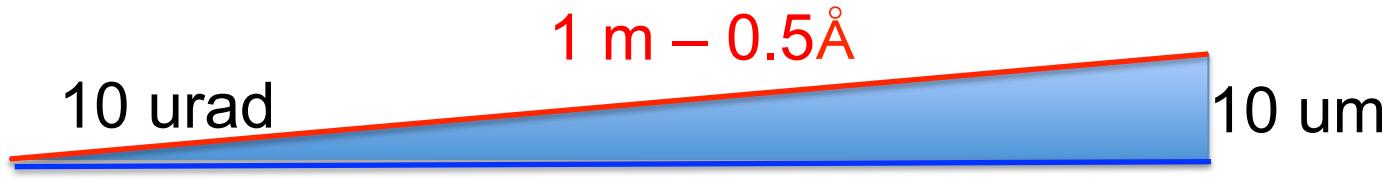
# SASE XFEL Scheme



To work optical cavity-free system we need  
“highly brilliant electron beam” and “ long  
undulator with a large number of periods”

### <Brilliant electron beam>

High electron density achieving a high gain and low angular divergence keeping density modulation of Å order.



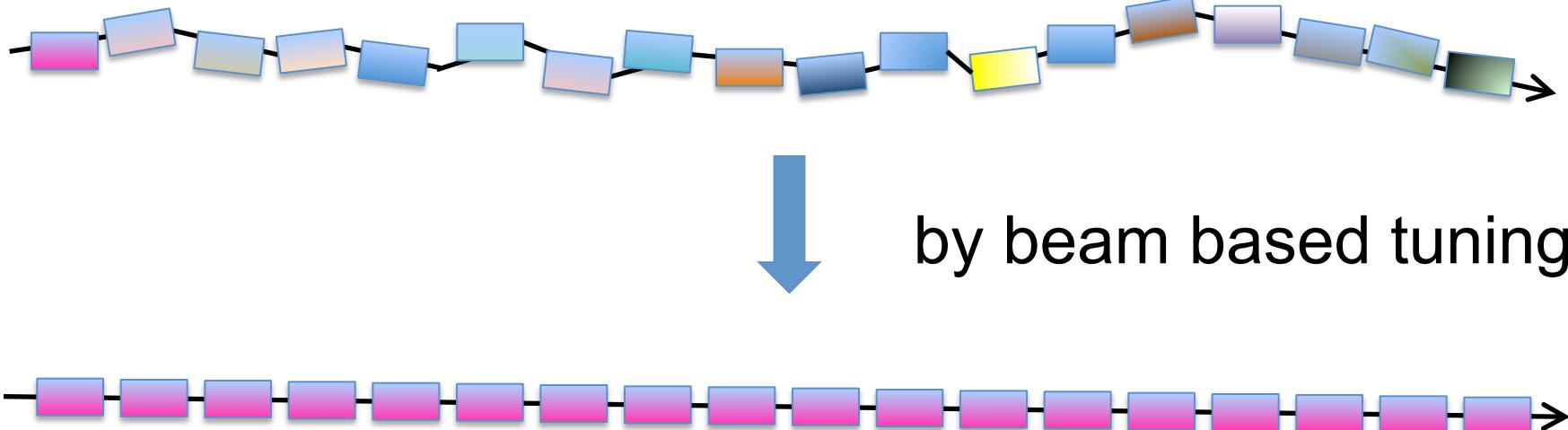
### <Long undulator>

A larger number of periods realizes a sufficiently high gain by a single pass, which corresponds to that obtained by the optical cavity system.

# Long undulator comprising of 18 segments has To behave as a single undulator

For this purpose,

- 18 segments with identical performances (single color)
- Undulator segments alignment (alignment of squares)
- Straight e-beam trajectory (black straight line)



To access short laser wavelength we need  
“high energy electron beam” , “appropriate  
period undulators” and large K-value

<High energy electron beam>

Undulator radiation wavelength depending on the  
inverse of gamma square

<Short period undulators>

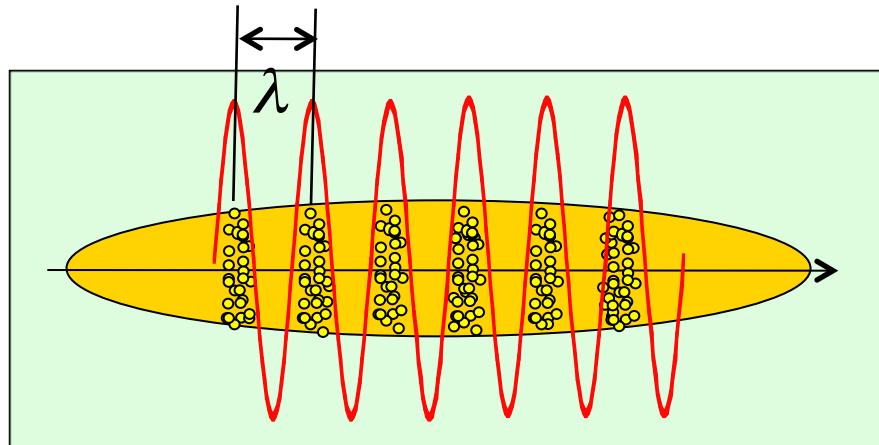
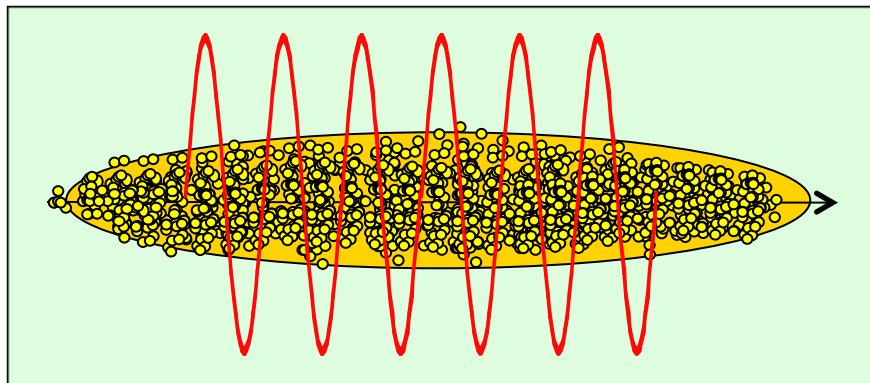
Undulator radiation (laser) wavelength being  
proportional to the undulator period

# Free electrons as a laser medium

**Resonance condition**

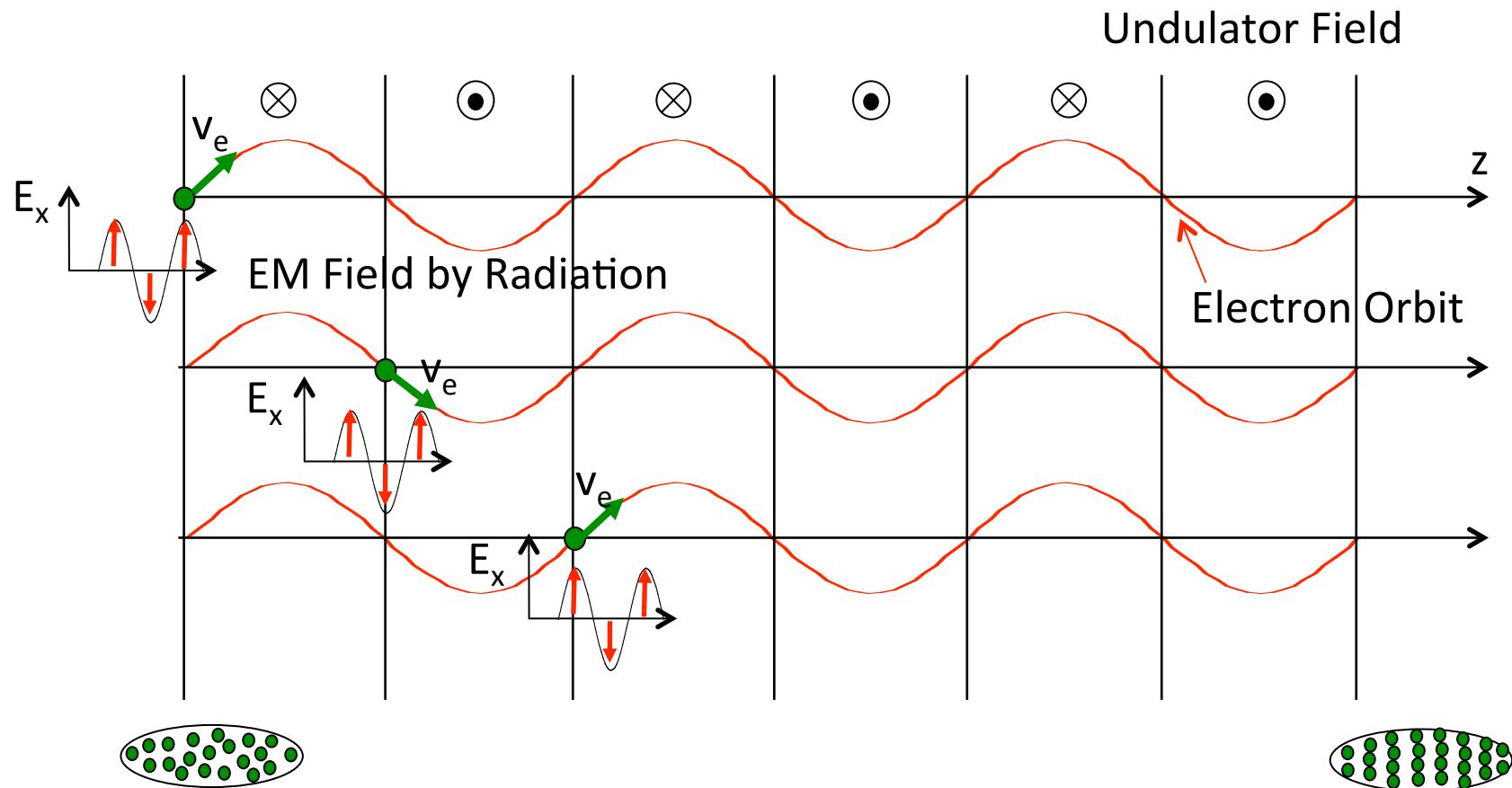
$$\lambda = \lambda_u - \bar{v}_z T \approx \frac{\lambda_u}{2\gamma^2} \left( 1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K = \frac{eB\lambda_u}{2\pi m_0 c \gamma}$$

Electron beam is trapped in an electro-magnetic potential and this potential generates energy modulation around the stable fixed point. Then the energy modulation is converted to density modulation through the energy dispersion of the undulator.



# Free electrons as a laser medium

## Developing density modulation



# Free electrons as a laser medium

Instead of stimulated emission, the density modulated electrons with an interval of a resonance wavelength  $\lambda$ , enables laser amplification.

- Independent on energy level in atoms and molecules -

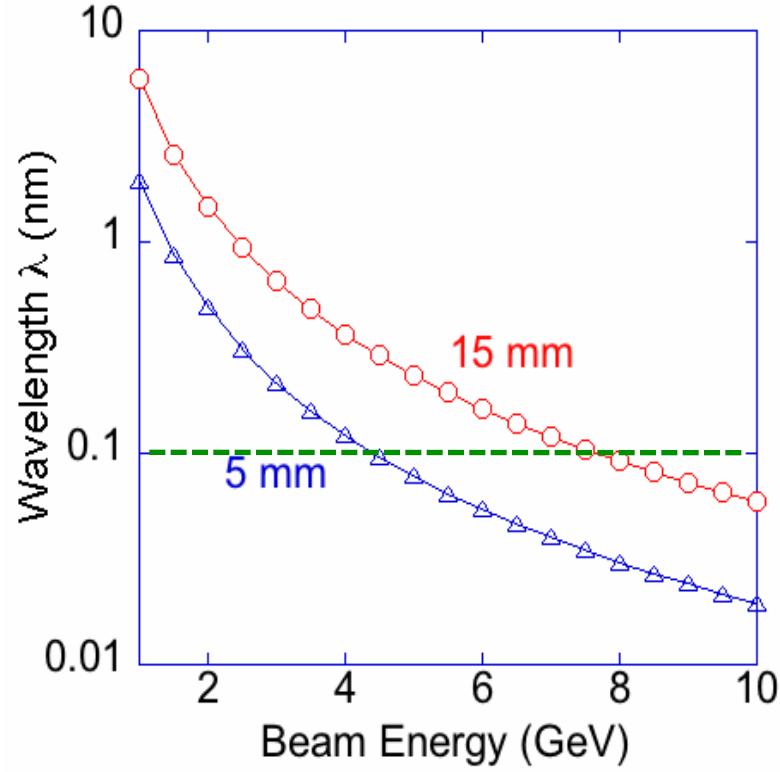
$$\lambda = \frac{\lambda_u}{2\gamma^2} \left( 1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right), K \approx 1 \sim 2$$

Let's estimate  $\lambda$  assuming

$$\begin{aligned}\lambda_u &= 15 \text{ mm}, K = 2, \\ \gamma &= 3915 @ 2 \text{ GeV}\end{aligned}$$



$$\lambda = 1.5 \text{ nm}$$



# Laser Amplification Gain

$$L_{1G} = \frac{\lambda_u}{4\sqrt{3}\pi\rho}, \quad \rho = \left( \frac{K}{4\gamma} \sqrt{F_1(K)} \frac{\Omega_\rho}{\omega_u} \right)^{\frac{2}{3}}, \quad \omega_u = \frac{2\pi c}{\lambda_u}, \quad n_e = \frac{N_e}{\sigma_\ell \sigma_x \sigma_y}.$$

$$F_1(K) = (J_0(\xi) - J_1(\xi))^2, \quad \xi = \frac{K^2}{2(1 + K^2)}, \quad \Omega_\rho = \left( \frac{4\pi c^2 r_e n_e}{\gamma} \right)^{\frac{1}{2}},$$

$$L_{1G} \propto \left( \frac{\langle \beta \rangle \varepsilon_{ns}}{I_p} \right)^{1/3}$$

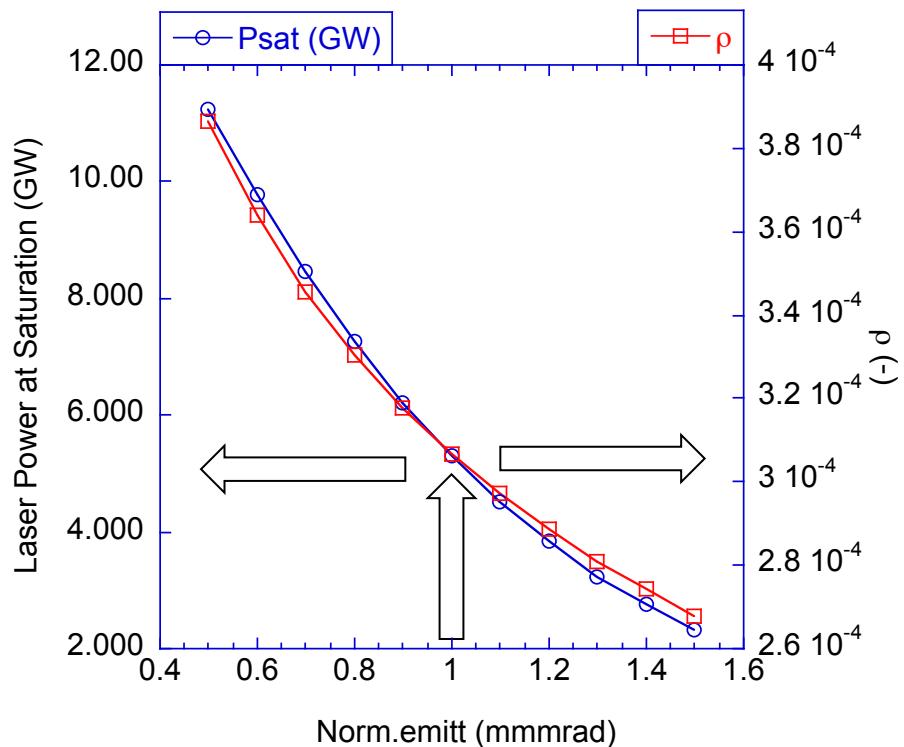
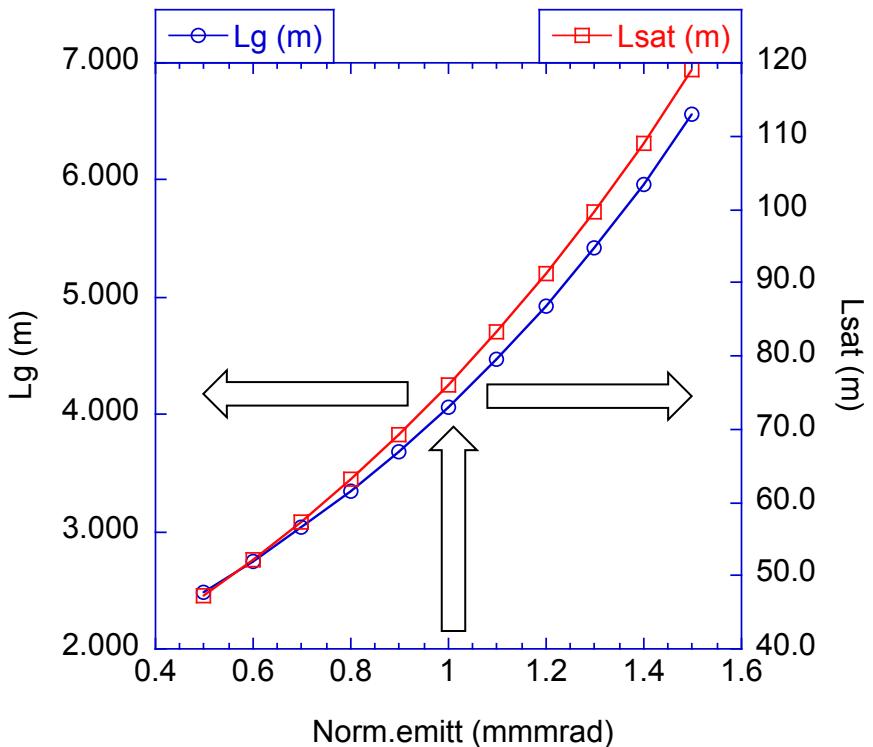
Normalized emittance at a lasing part

Peak current

For the higher gain,  
smaller emittance, higher  
beam current required

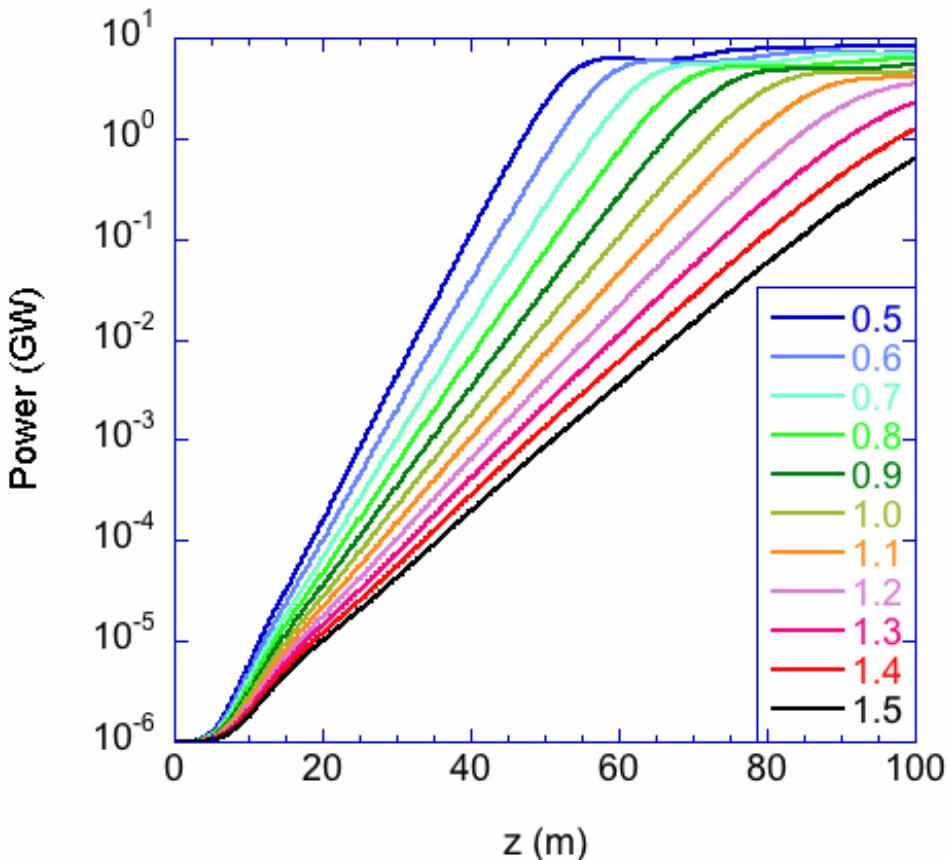
# Laser Amplification Gain

$\lambda_{\text{SASE}} = 1 \text{ \AA}$ ,  $K = 1.85$ ,  $\lambda_u = 18 \text{ mm}$ ,  $E = 8 \text{ GeV}$ ,  $I_p = 3 \text{ kA}$ ,  
 $\Delta E/E = 4 \times 10^{-5}$ ,  $\beta_{\text{ave}} \sim 30 \text{ m}$ ,



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For the higher laser power, accurate overlap between laser field and electron beam along a certain distance, 15 to 25 m

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# Future Perspective

Although variety of XFEL applications are expected , one facility can provide only a few BLs.

To widely utilize XFEL, it is essential to make the facility scale compact as much as we can. World's trend goes to this direction as XFEL usefulness becomes gradually clear.

# Leading three XFEL

# “Big three”

An aerial photograph showing the large circular particle accelerator ring of the European XFEL facility, surrounded by green fields and industrial buildings. The text "Euro-XFEL (2014~)" and "High rep rate ~3.4 km" is overlaid on the image.



# SASE XFELs under operation & construction in 3-sites

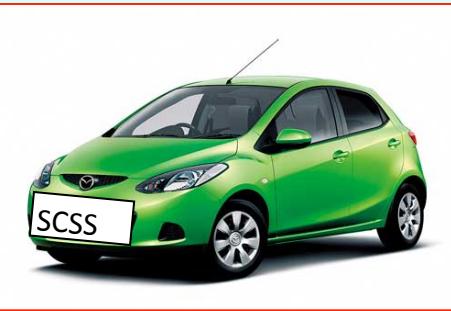


# XFEL@SPring-8 (2012~) Compact



# Development Target

*SPring-8 Compact SASE Source  
(SCSS) Concept*



*Compact , cheaper,  
but high-performance*

**versus**



# Wavelength of undulator radiation,

$$\lambda = \frac{\lambda_u}{2n\gamma^2} \left( 1 + \frac{K^2}{2} + \gamma^2 \theta^2 \right)$$

To generate X-ray with **lower beam energy** requires a **shorter undulator period** and **smaller K-value**

# Design Concept of SPring-8 Compact SASE Source (SCSS)



Lower Beam Energy



Size Reduction



Efficient Acceleration



Further Size Reduction

+  
Smaller  
K

Smaller Normalized  
Beam Emittance



Short period  
in-vacuum  
undulator

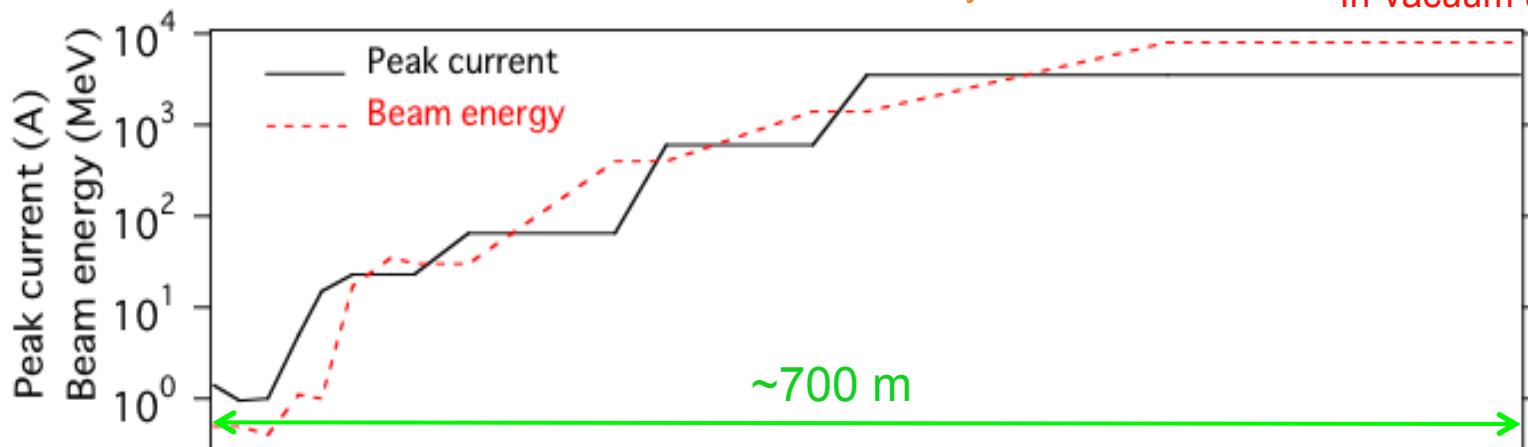
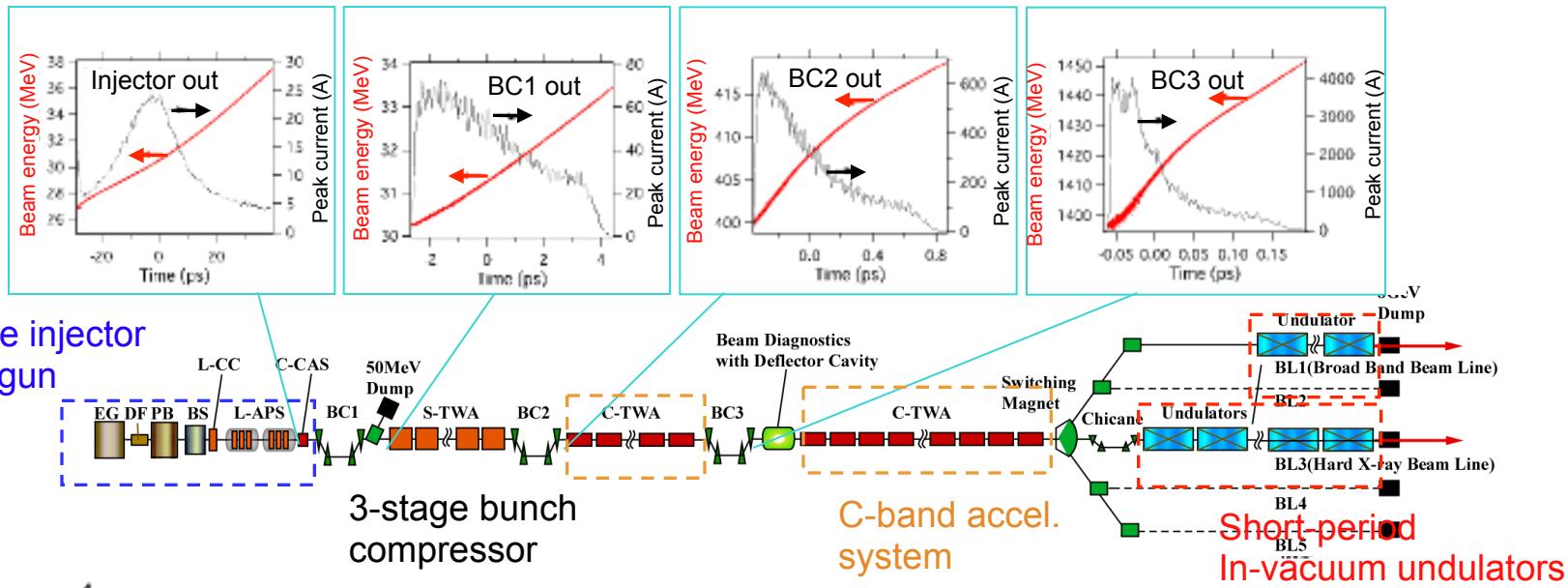


C-band high  
gradient  
acceleration  
system



Thermionic  
gun based  
low emittance  
injector

# Compact design for 8-GeV SASE XFEL



# Design Performance of XFEL

## Comparison with SPring-8 performance

Parameter	XFEL	SPring-8
• Wavelength(fundamental)	>0.06 Å	>0.05 Å
• Pulse Duration	<100 fs	~40 ps
• Repitition	$\leq$ 60 Hz	~40 MHz
• Spatial Coherence	100%	~0.1%
• Peak Power	20~30 GW	100~200 W
• Peak Brilliance	$\sim 10^{34}$	$\sim 10^{24}$
• Averaged Brilliance	$\sim 10^{22}$	$\sim 10^{21}$

Def of Brilliance : phs/sec/mrad<sup>2</sup>/mm<sup>2</sup>

**XFEL/SPring-8 Beamline Technical Design Report Ver. 1.0, June 17 (2008)**

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# History of SACL

2006~2010 XFEL construction

2011 Feb. 21 Beam commissioning started

Jun. 7 First lasing at 0.12 nm  
achieved

Oct. SASE power saturation  
achieved at 0.12 nm



2012 Mar. 1 User experiments officially started

2013 Apr. 2-Color SASE released to user experiments

Oct. SASE intensity beyond 0.5 mJ/pulse achieved

Nov. First experimental symptom of seeding observed

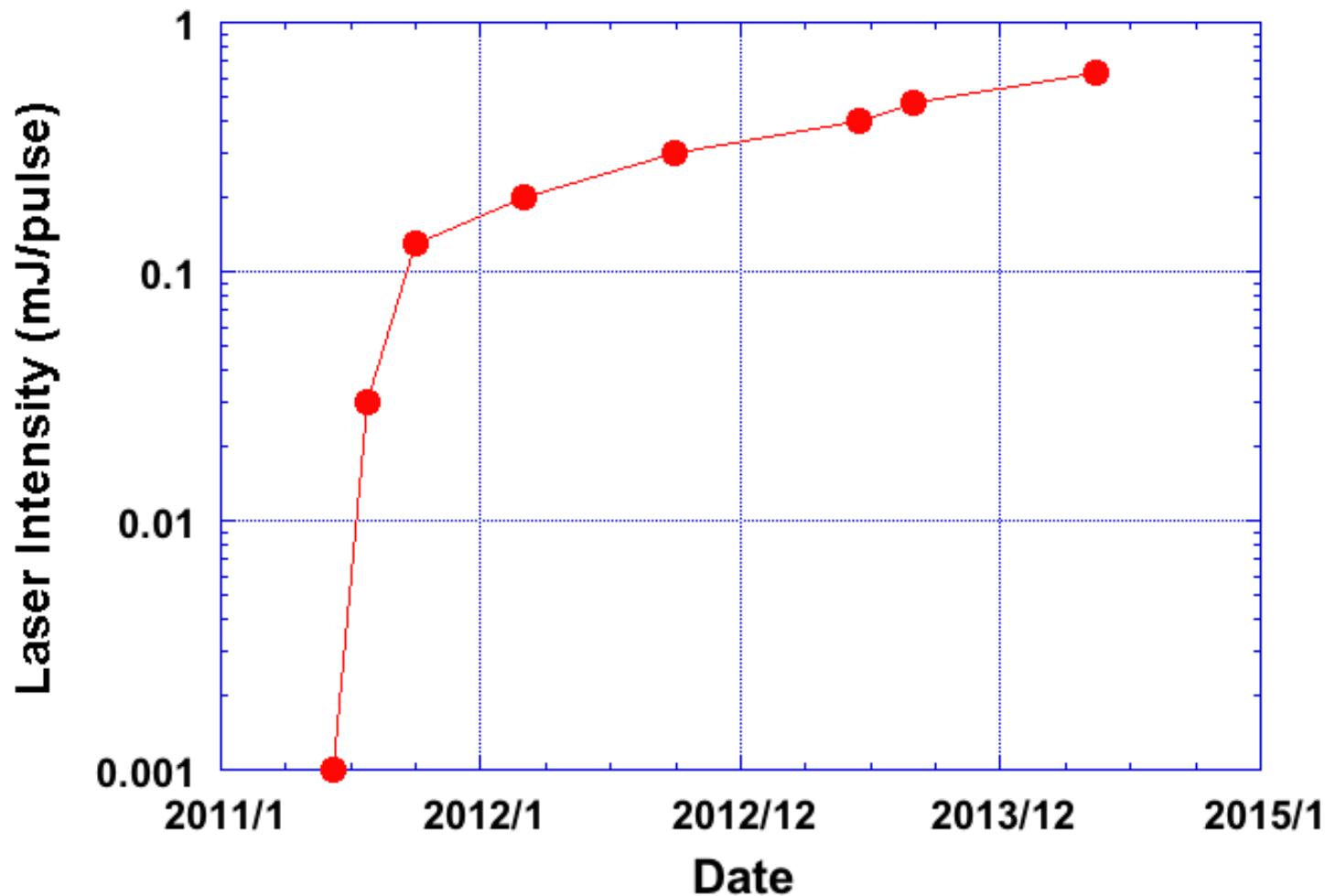
2014 Apr. Circularly-polarized SASE released to user experiments

# Summary of Present Performance

Pulse Energy <sup>*</sup> :	Sub-m J, ~0.6mJ@10keV
Peak Power <sup>*</sup> :	>60 GW (e-beam, <10 fs in FWHM)
Intensity Fluctuation <sup>*</sup> :	~10% ( $\sigma$ )
Lasing Wavelength:	0.83 - 2.8 Å (user operation)
Spatial Coherence:	nearly full
Repetition:	30 Hz (Max.60 Hz)
Mean Fault Interval:	30~40 min
Recovery time:	1 min.
Operation mode:	24 hr continuous
Reproducibility:	~70% of the peak

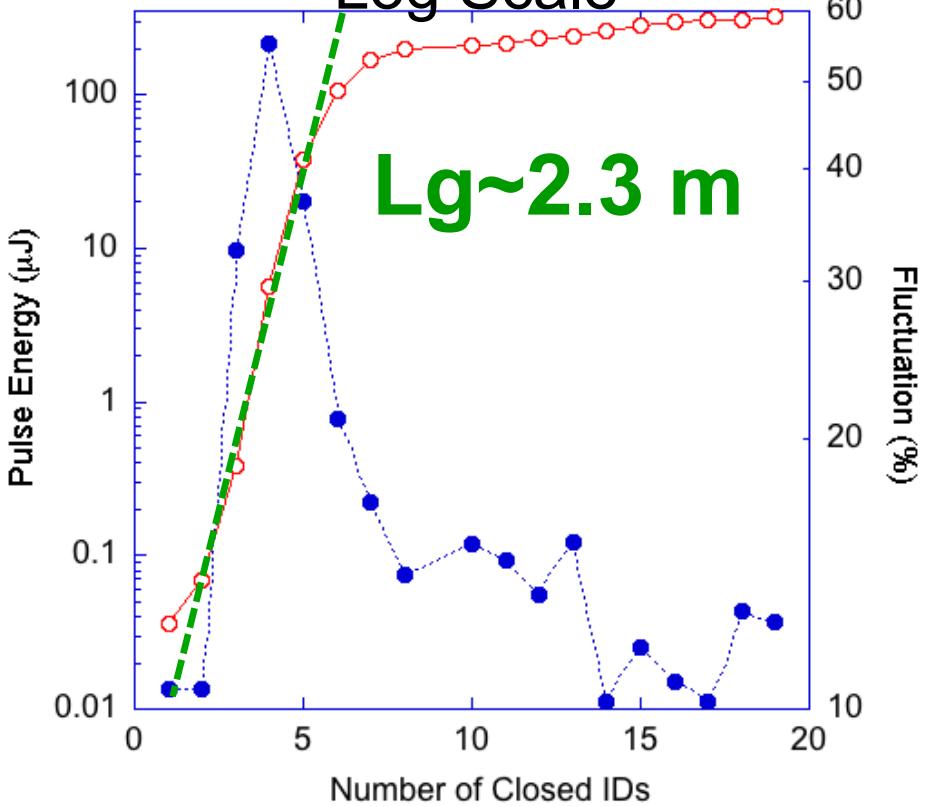
\*It depends on the condition

# Evolution of SASE Intensity

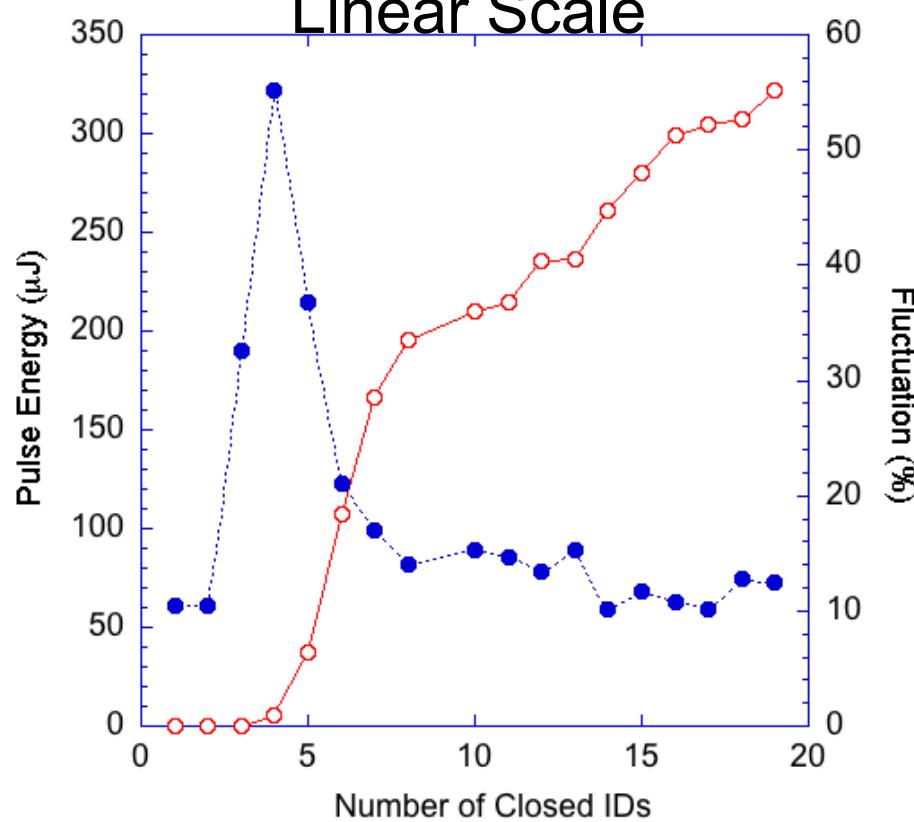


# Gain Curve

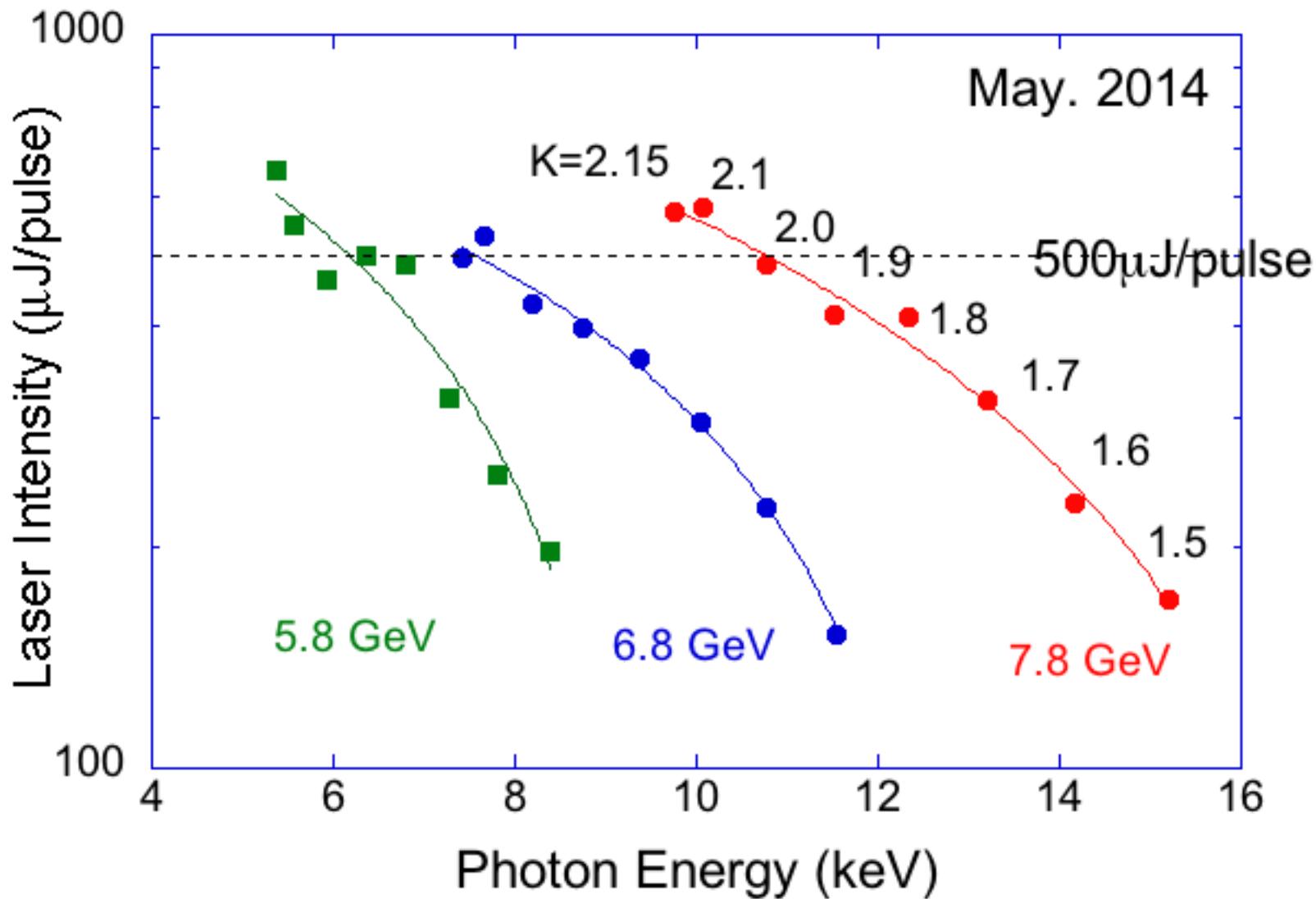
Log Scale



Linear Scale



# Laser Intensity vs Wavelength(old data)

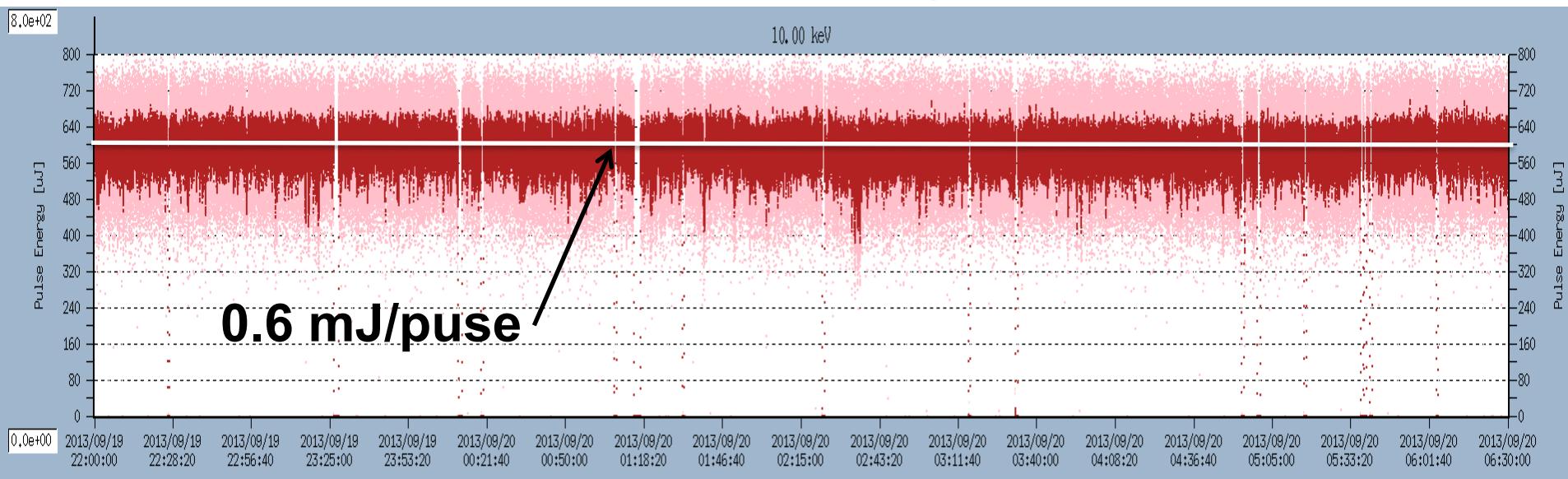


# Laser Stability

Laser availability in user experimental run is beyond 90%

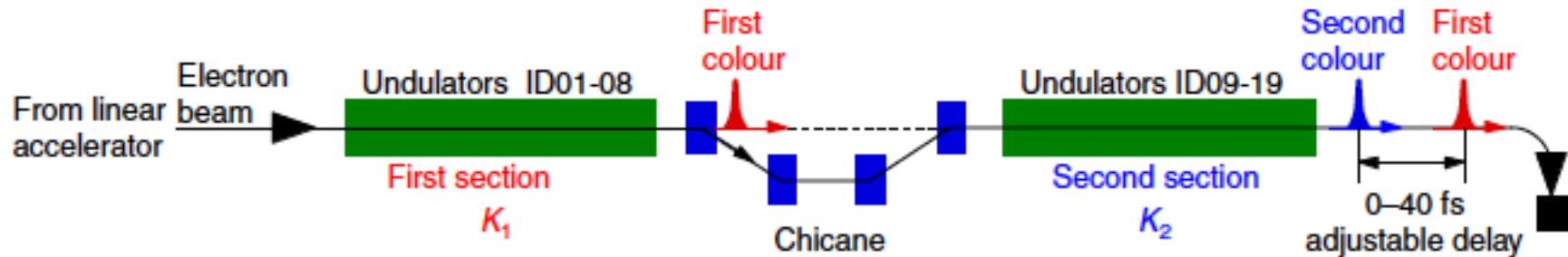
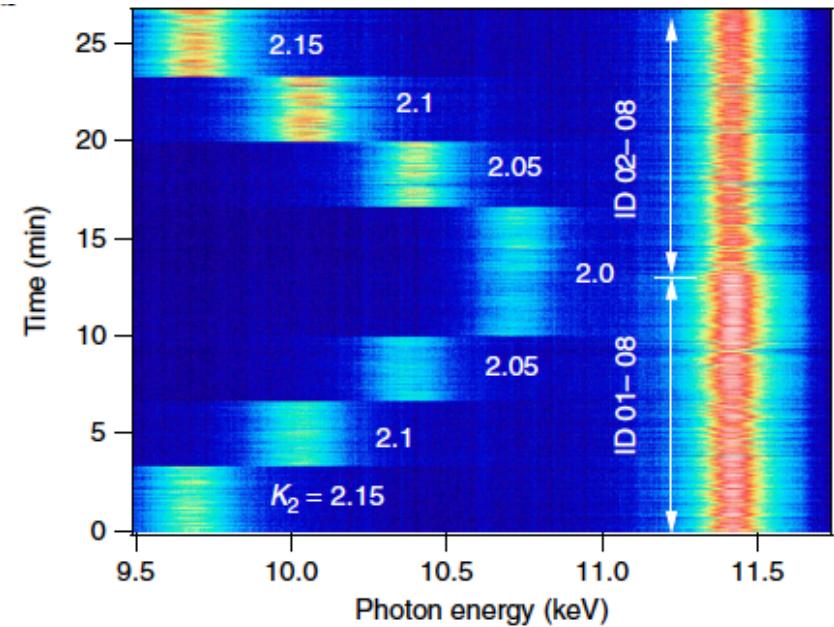
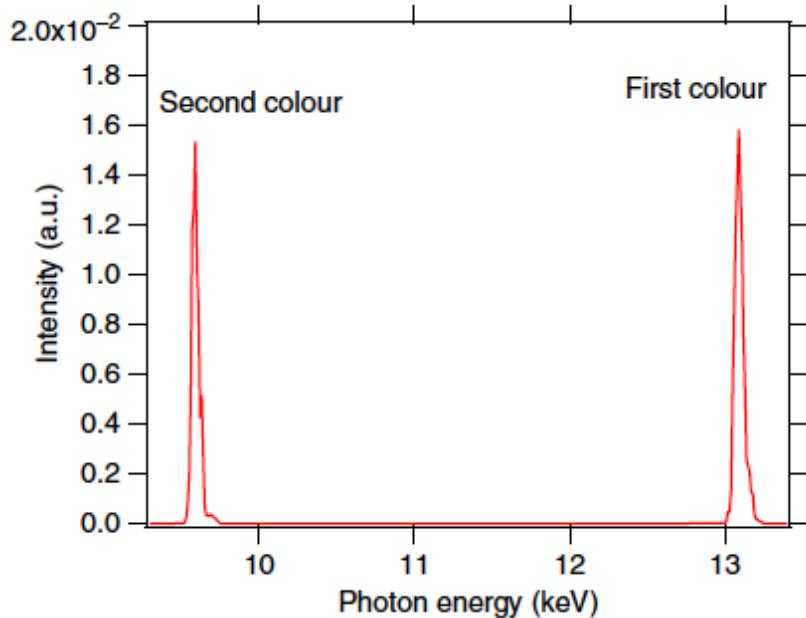
@10 keV

About 8 hr



# 2-Color SASE Routinely Available

- Wavelength separation of up to 30%
- X-ray wavelength region
- Precise delay control with an attosecond resolution



# Outline of System Upgrade

